



Π	Type	Ľ	Hits	Search Text	DBs	Time Stamp		Comments
٦	BRS	L1	382	hsg	USPAT	19	1999/11/11 15:24	-
2	BRS	L2	44400	1100	USPAT	19	1999/11/11 15:25	
ω	BRS	L3	9557	1222	USPAT	19	1999/11/11 15:26	드
4	BRS	L4	276828	1200 1300 1400 1500 1600 1700	USPAT	19	1999/11/11 15:28	_ = [
5	BRS	L5	74247	1040 1050 1060 1070	USPAT	ㅂ	1999/11/11 15:27	999/11/11 15:27
6	BRS	91	33114	1025 1035 1045 1055 1065 1075	USPAT	ш	1999/11/11 15:28	999/11/11 15:28
7	BRS	L7	61037	1105 1205 1305 1405 1505 1605 1705 1805 1905	USPAT	1	1999/11/11 15:29	\vdash
8	BRS	81	5221	(4 5 6 7) adj2 (degree degrees c centigrade centegrade celsius)	USPAT	<u> </u>	1999/11/11 15:34	
9	BRS	Г9	329813	substrate substrates wafer wafers	USPAT	1.9	1999/11/11 15:35	-
10	BRS	L10	1717	8 and 9	USPAT	1.9	1999/11/11 15:36	دسز
11	BRS	L11	77903	sin or si adj n si.sub? nitride	USPAT	1.0	1999/11/11 15:38	999/11/11 15:38
12	BRS	և12	19	8 near6 11 and 9	USPAT	19	1999/11/11 15:45	1 15:45
13	BRS	L13	8043	(plasma plasmas) same 11	USPAT	19	1999/11/11 15:46	99/11/11 15:46
14	BRS	L14	22	(plasma plasmas) same 11 same 8	USPAT	1	1999/11/11 15:46	999/11/11 15:46

9	ω	7	Q	U	4	ω	Ν	1	
L9	18	ъ7	16	Ь5	L4	L3	L2	L1	L #
17	270647	336767 4	153	33665	121770 5	241	101926	1522	Hits
rpecvd	7 same 4	heat\$ or temperature	5 and 1	2 same 4	wafer or substrate	1 and 2	(silicon adj nitride) or sin or (si adj2 3 adj2 n)	plasma same remot\$	Search Text
USPAT; USOCR; EPO; JPO; Derwent		USPAT; USOCR; EPO; JPO; Derwent		DBs					
1999/11/11 09:54	1999/11/11 09:54	1999/11/11 09:50	1999/11/11 09:18	1999/11/11 09:12	1999/11/11 09:10	1999/11/11 09:09	1999/11/11 09:05	1999/11/11 08:57	Time Stamp